

Supporting Information

Mechanism Investigation of the Post Necking Treatment to WO₃ Photoelectrodes

Dapeng Cao,^[a,b] Jie Wang,^[a] Jingbo Zhang,^[a] Shuaishuai Liu,^[a] Futing Xu,^[a] Song
Xu,^[a] Xin Xu,^[a] Baoxiu Mi, ^{*[a]} Zhiqiang Gao^{*[b]}

*[a] Key Laboratory for Organic Electronics & Information Displays (KLOEID),
Jiangsu Engineering Centre for Plate Displays & Solid State Lighting, and Institute of
Advanced Materials (IAM), Nanjing University of Posts & Telecommunications,
Nanjing 210023, China*

*[b] Key Laboratory of Flexible Electronics, Jiangsu National Synergetic Innovation
Center for Advanced Materials (SICAM), School of Material Science and
Engineering, Nanjing University of Posts & Telecommunications, Nanjing, Jiangsu
210023, China.*

Corresponding Author

*E-mail: iambxmi@njupt.edu.cn; iamzqgao@njupt.edu.cn.

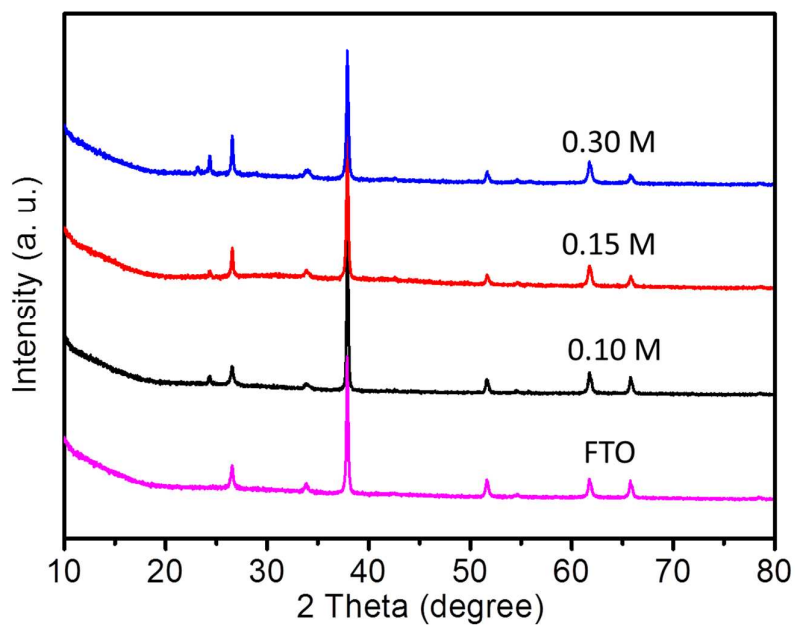


Figure S1. The XRD pattern of compact WO_3 films on FTO prepared from different concentration of ammonium metatungstate. The diffraction pattern of a bare FTO is shown for comparison.

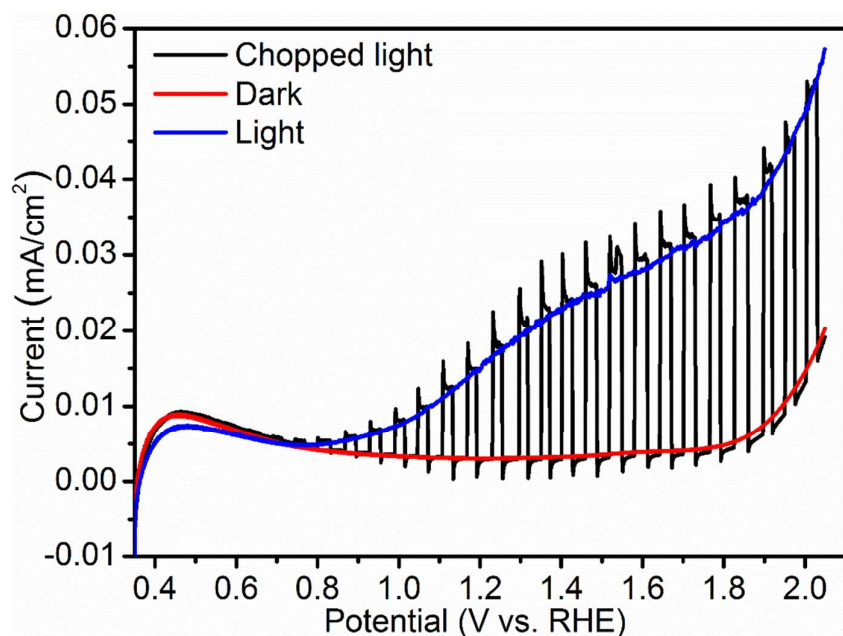


Figure S2. The current-potential curve of a WO_3 photoanode prepared by drop ammonium metatungstate followed by annealing.

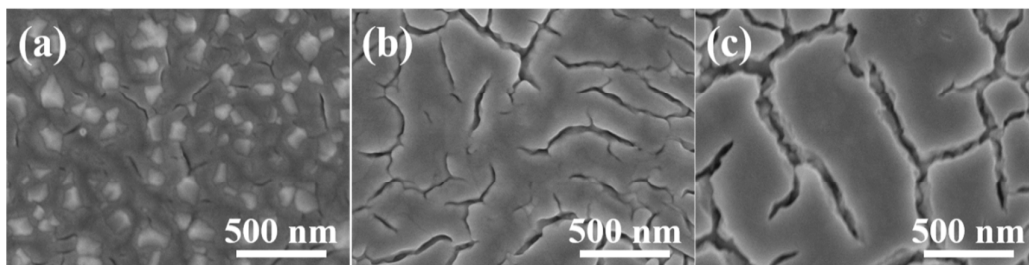


Figure S3. SEM images of the compact WO_3 layers prepared by spin-coating ammonium metatungstate solution on FTO followed by annealing at 450 °C in air. The concentration of ammonium metatungstate solution is 0.1 M (a), 0.15 M (b) and 0.3 M (c).

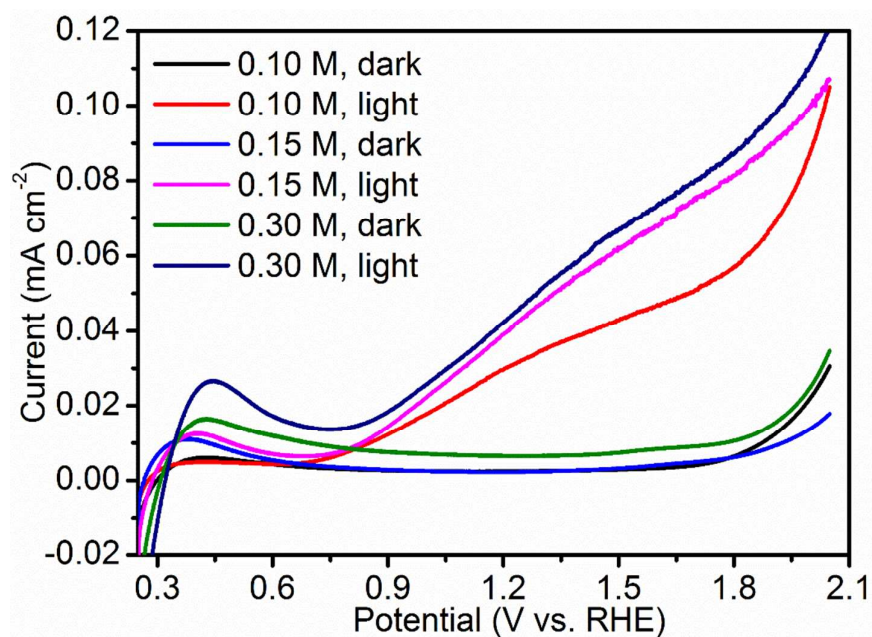


Figure S4. The current-potential curves of WO_3 photoanodes prepared by spin-coating ammonium metatungstate solution on FTO followed by annealing at 450 °C in air.

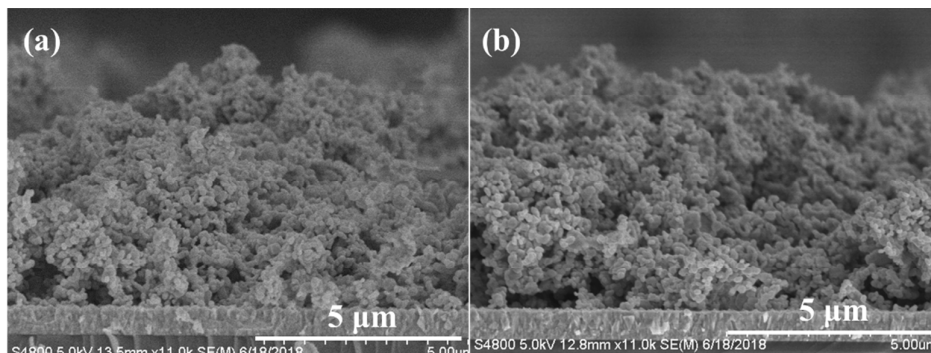


Figure S5. Section SEM images of the WO₃ films without (a) and with (b) a compact WO₃ layer.

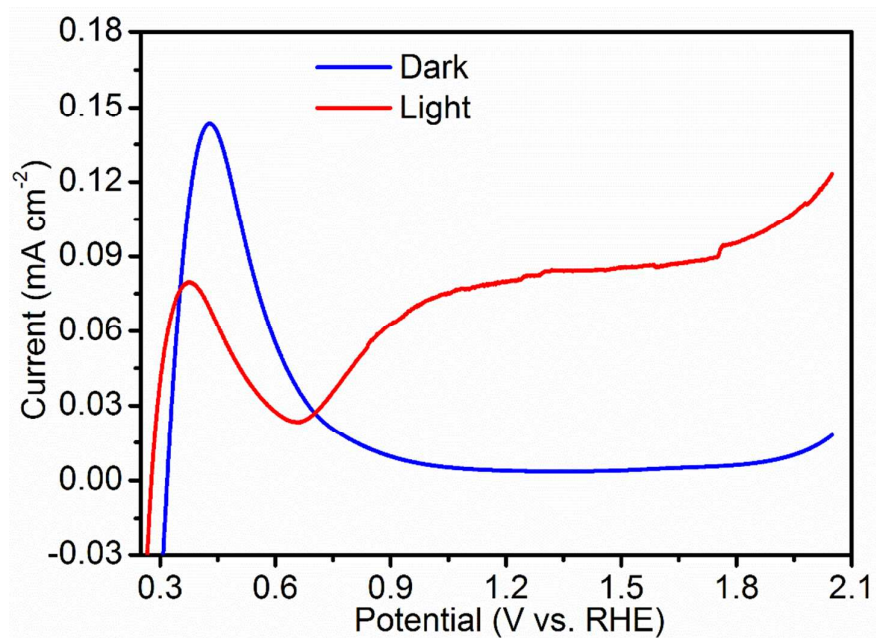


Figure S6. Current-potential curves of an as-deposited WO₃ photoanode with compact layer.

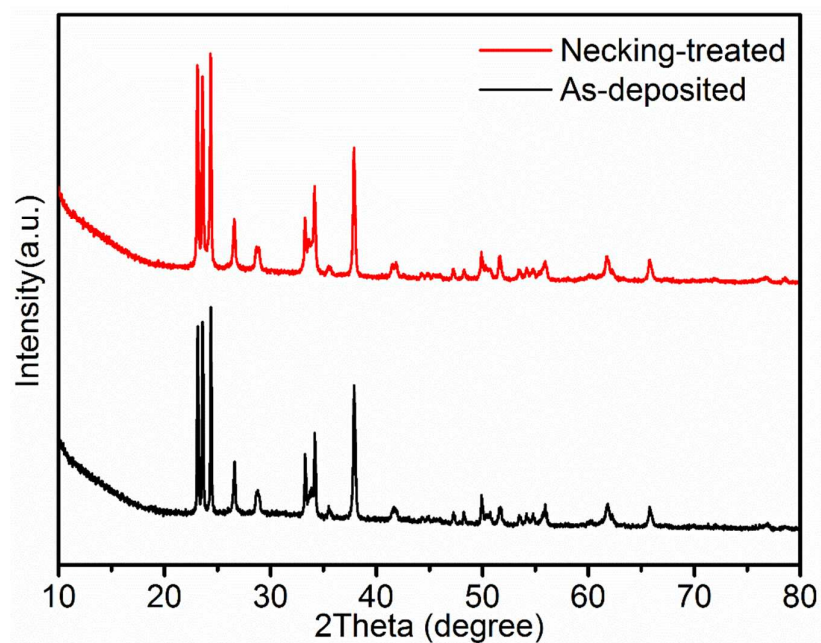


Figure S7. XRD pattern of as-deposited and necking-treated WO₃ films.

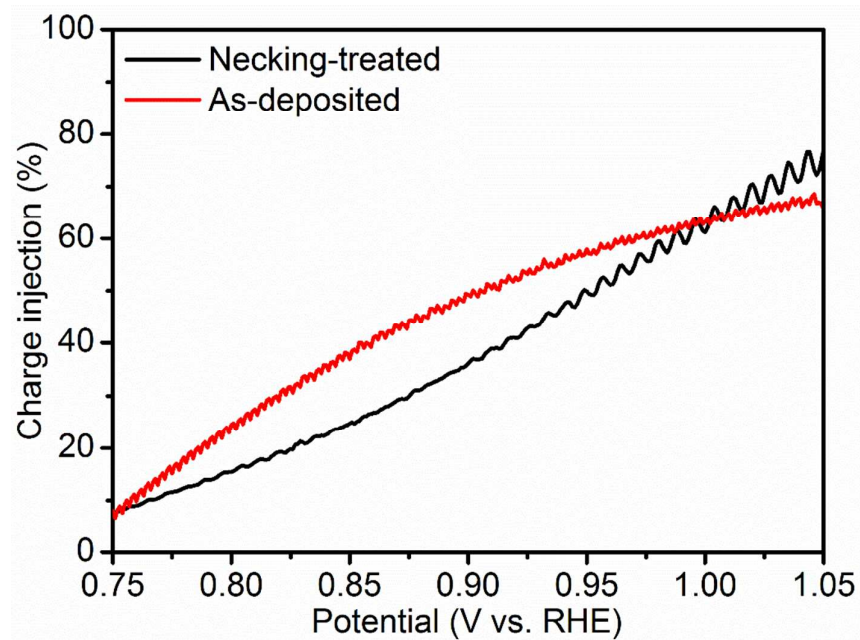


Figure S8. Yield of charge injection in the as-deposited WO_3 photoanode and the necking-treated WO_3 photoanode.

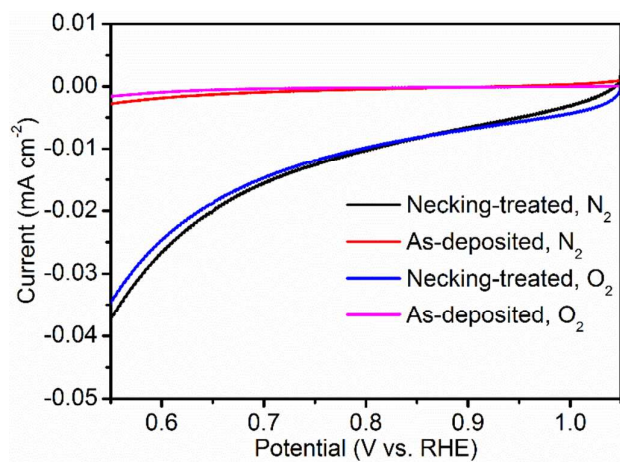


Figure S9. Reduction dark current on the as-deposited and necking-treated samples, electrolyte: 0.5 M Na_2SO_4 with N_2 or O_2 bubbling.

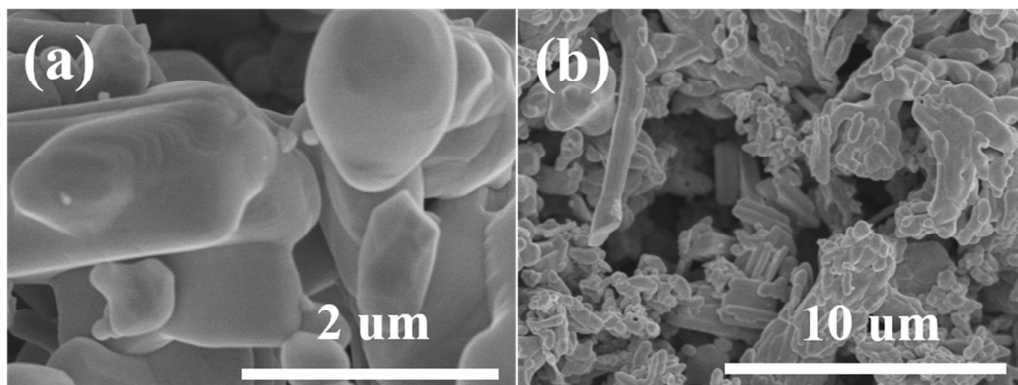


Figure S10. SEM images of a WO_3 photoanode prepared from large WO_3 particles at high (a) and low (b) magnification.

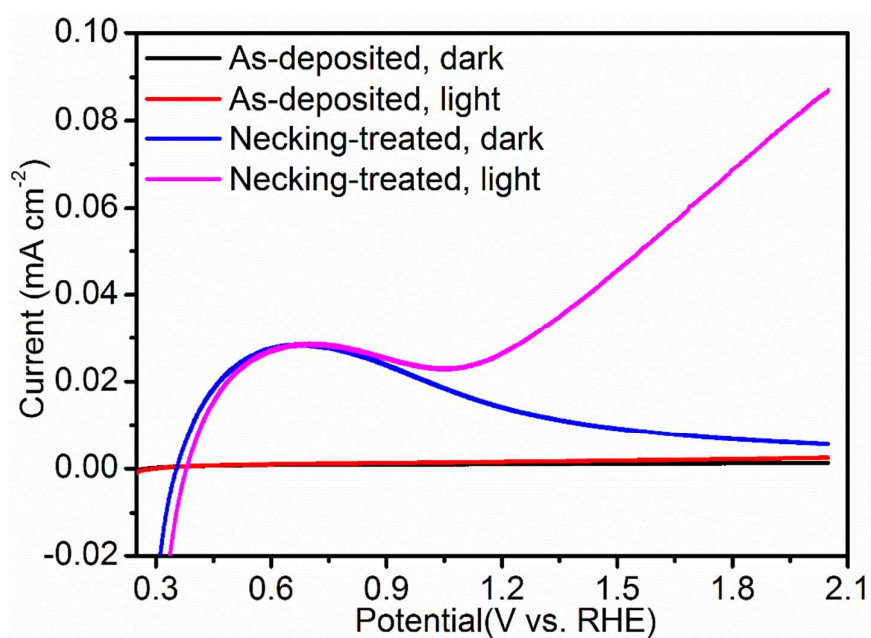


Figure S11. Current-potential curves of the WO_3 photoanodes (prepared from large WO_3 particles) without and with post necking treatment.

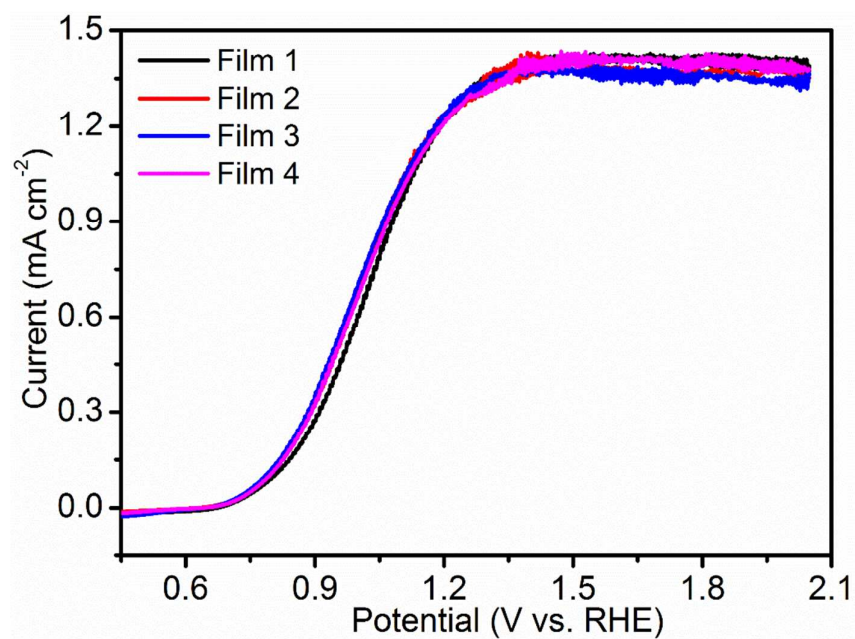


Figure S12. Current-potential curves of the necking-treated WO_3 photoanode with underlayer in 0.5 M Na_2SO_4 aqueous solution.

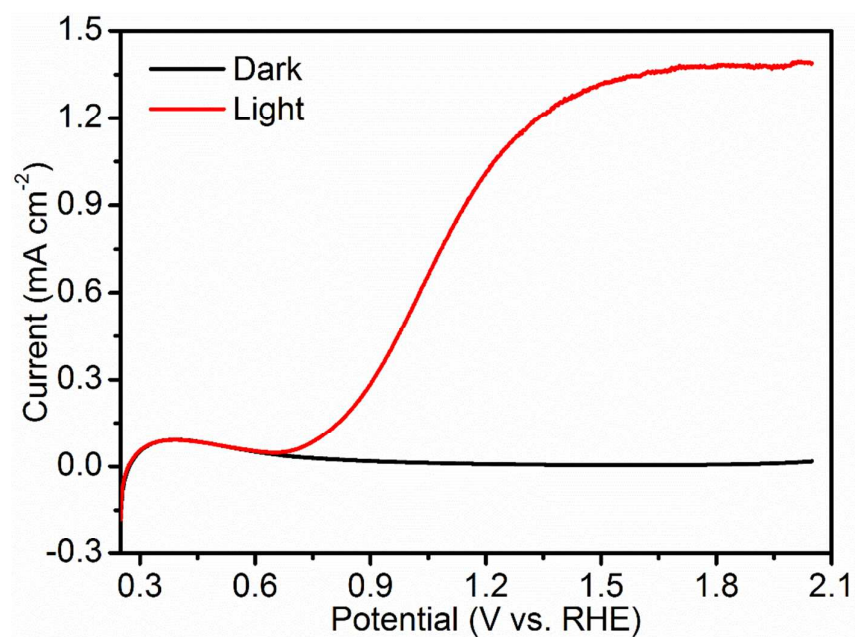


Figure S13. Current-potential curves of the necking-treated WO_3 photoanode after I - t test.

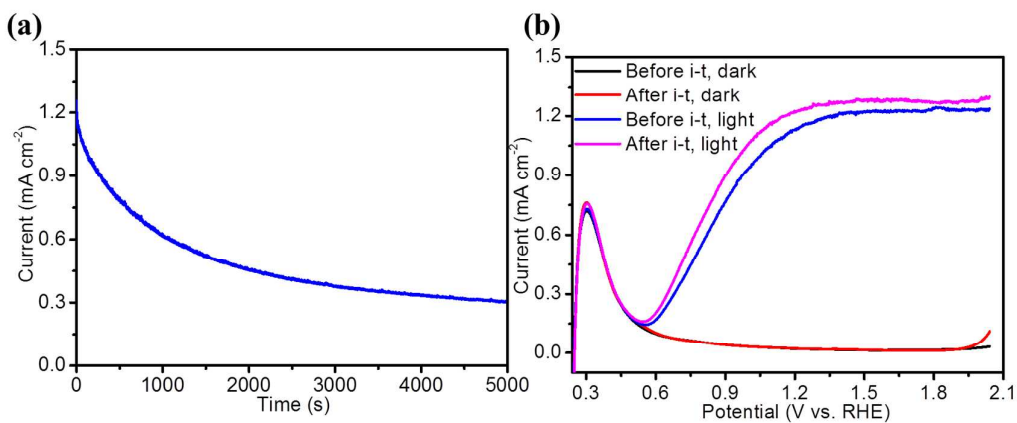


Figure S14. (a) *I-t* curves of the necking-treated WO₃ photoanode with underlayer at a potential of 1.65 V_{RHE}, (b) *I-V* curves of the necking-treated WO₃ photoanode with underlayer before and after the *I-t* test, electrolyte: 0.5 M H₂SO₄.